

METHOD OF FABRICATING FLASH MEMORY DEVICES

BACKGROUND OF THE INVENTION

1. Field of the Invention

The present invention relates to a method of fabricating a FLASH memory device, and more particularly to a method of fabricating a FLASH memory device including a split gate.

2. Discussion of Related Art

FLASH memory devices can electrically write or erase data. FLASH memory devices maintain data without a power supply. Therefore, the FLASH memory devices have been widely used in various technologies. FLASH memory devices can be classified into NAND type and NOR type devices according to a structure of a memory cell array. Comparatively, NAND type FLASH memory devices can be highly integrated within a unit area of a circuit and NOR type FLASH memory devices have a fast response speed.

In NOR type FLASH memory devices, memory cells are arranged along rows and columns, a plurality of bit lines are disposed parallel to the rows and a plurality of word lines are disposed parallel to columns. The memory cells in each of the rows are connected to a bit line in parallel and the memory cells in each of the columns are connected to a word line in parallel.

A memory cell of a NOR type FLASH memory device is selected by selecting a word line and a bit line. Accordingly, the memory cells of NOR type FLASH memory devices can be accessed randomly, so that the response

speed thereof is faster than that of the NAND type FLASH memory device. In the NOR type FLASH memory device, a plurality of memory cells are connected to a bit line in parallel, so that if a memory cell transistor connected to the bit line is erased, current passes through the bit line regardless of a state of a selected memory cell. Therefore, each memory cell that is connected to the bit line is read as if the memory cells are in a turned-on state.

A split gate type FLASH memory device is another type of FLASH memory device. Word lines of the split gate type FLASH memory device act as a selection gate and a control gate, overlap a portion of a floating gate.

Fig. 1A is a top plane view of a conventional split gate type FLASH memory device.

Referring to Fig. 1A, device isolation layers 8 are disposed to define first and second active regions 12a and 12b, which intersect each other. A pair of floating gate patterns 14 are disposed on each first active region 12a between adjacent second active regions 12b. Word lines 18 crossing over the first active regions 12a are disposed on the floating gate patterns 14. The word lines 18 lie on top of the floating gate patterns 14 and on the first active regions 12a beside a sidewall of the floating gate patterns 14. Drain regions are formed in the first active regions 12a between adjacent word lines 18 and a bit line plug 20 is connected to each drain region.

Referring to Fig. 1B, after active regions 12a and 12b are defined in a substrate, a conductive layer is formed. The conductive layer is patterned to form a floating gate 14 of the conventional split gate type nonvolatile memory

device. Edges of a pattern formed by a photolithographic process are rounded due to a proximity effect even though the pattern is designed to be rectangular in layout. As illustrated in the Fig. 1B, a width of the elliptical floating gate pattern may reduced at the edges, so that when the floating gate pattern is 5 misaligned, a channel under the floating gate decreases in width and influences characteristics of the memory cell. Thus, variations in cell characteristics in a cell array may be widened. Referring to Fig. 1C, if a width of the active region becomes narrow due to a high integration of the semiconductor device, a 10 misalignment of the floating gate causes a direct contact of a word line 18 and a substrate 10 between a device isolation layer 8 and the floating gate pattern 14. In addition, the floating gates of the adjoining memory cells connected to 15 adjoining bit lines needs to be separated from each other on the device isolation layer by a predetermined distance, so that the distance between the adjoining floating gates should be defined wider than a minimum line width. Therefore, the width of the device isolation pattern 8 may not be reduced to a minimum line width.

Summary of the Invention

According to an embodiment of the present invention, a split gate type 20 FLASH memory device is formed comprising floating gate patterns thereof without harmful influence of a misalignment or a proximity effect during a photolithographic process.

According to an embodiment of the present invention, a method of

forming a split gate type FLASH memory device minimizes variations in cell characteristics in a cell array.

According to an embodiment of the present invention, there are provided methods of fabricating a split gate type FLASH memory device including floating gates with sidewalls aligned to sidewalls of a trench device isolation layer. The methods comprise forming trench device isolation layers to define a plurality of parallel first active regions. A gate insulation pattern, a conductive pattern and a hard mask pattern, which are sequentially stacked and include sidewalls aligned to sidewalls of the trench device isolation layer, are formed on the first active region. The hard mask pattern is removed at regular intervals along each first active region so as to expose a top of the conductive pattern. An oxide pattern is formed on the exposed conductive pattern and the hard mask pattern is removed. Using the oxide pattern as an etch mask, the conductive pattern is etched to form floating gate patterns disposed on each first active region at regular intervals. Tunnel oxide layers are formed on sidewalls of the floating gate pattern and a plurality of control gate electrodes are formed, crossing over the first active regions. The control gate electrodes are disposed on the floating gate patterns.

20 Brief Description of the Drawings

Preferred embodiments of the present invention will be described below in more detail, with reference to the accompanying drawings:

Figs. 1A is a top plane view of a conventional split gate type FLASH

memory device.

Fig. 1B shows a conventional split gate type FLASH memory device.

Fig. 1C is a cross-sectional view taken along a line A-A of Fig. 1A.

Fig. 2 is a top plane view of a split gate type FLASH memory device
5 according to an embodiment of the present invention.

Figs. 3A-9A are top plane views showing methods of fabricating a split
gate type FLASH memory device according to an embodiment of the present
invention

Figs. 3B-9B are cross-sectional views taken along a line B-B of Figs.
10 3A-9A.

Figs. 3C-9C are cross-sectional views taken along a line C-C of Figs.
3A-9A.

Detailed Description of Preferred Embodiments

15 The present invention will be described more fully hereinafter with
reference to the accompanying drawings, in which preferred embodiments of
the invention are shown. This invention, however, may be embodied in many
different forms and should not be construed as limited to the embodiments set
forth herein. Rather, these embodiments are provided so that this disclosure
20 will be thorough and complete, and will fully convey the scope of the
invention to those skilled in the art. In the drawings, the thickness of layers
and regions are exaggerated for clarity. It will also be understood that when a
layer is referred to as being "on" another layer or substrate, it can be directly

on the other layer or substrate, or intervening layers may also be present. Like numbers refer to like elements throughout.

Fig. 2 is a plane view of a NOR type split gate FLASH memory device in accordance with an exemplary embodiment of the present invention.

Referring to Fig. 2, a spilt gate type FLASH memory device includes device isolation layers 58 disposed in a substrate to define a plurality of first active regions 62a that are parallel to each other. Floating gate patterns 64 are disposed on the first active regions 62a at regular intervals. A plurality of parallel word lines 68 crossing over the first active regions 62a are disposed on the floating gate patterns 64. The word lines 68 lie on a plurality of floating gate patterns 64 and the first active regions 62a beside a sidewall of each of the plurality of floating gate patterns 64.

The device isolation layer 58 defines a plurality of second active regions 62b that are parallel to each other and cross the first active regions 62a. A pair of floating gate patterns 64 are disposed on each of the first active regions 62a between intersections of the first and second active regions 62a and 62b. Drain regions are formed in each first active region 62a between the word lines 68 lying on the first active regions 62a. Source regions are formed in each second active region 62b between the word lines lying on the first active regions 62a. A bit line plug 70 is disposed on each drain region. Therefore, the source region comprises a shared source region where memory cells at both sides of the source region are connected in parallel. A shared source pattern connected to the first active regions 62a may be disposed in the

position of the second active regions 62b, replacing the second active regions 62b. In exemplary embodiment of the present invention, the device isolation layer 58 is formed with a trench structure and the floating gate pattern 64 includes sidewalls aligned to sidewalls of the device isolation layer 58.

5 Figs. 3A-9A are top plane views illustrating a method of fabricating a split gate type FLASH memory device in accordance with the exemplary embodiment of the present invention.

Figs. 3B-9B are cross-sectional views taken along a line B-B of Figs. 3A-9A, respectively.

10 Figs. 3C-9C are cross-sectional views taken along a line C-C of Figs. 3A-9A.

Referring to Figs. 3A, 3B and 3C, a gate insulation layer 52, a conductive layer 54 and a hard mask layer 56 are stacked on a substrate 50. The gate insulation layer 52 may be formed of silicon oxide, silicon oxynitride or the like, the conductive layer 54 may be formed of polysilicon and the hard mask layer 56 may be formed of silicon nitride.

15 Referring to Figs. 4A, 4B and 4C, the hard mask layer 56, the conductive layer 54 and the gate insulation layer 52 are patterned to form a plurality of parallel patterns comprising a gate insulation pattern 52a, a conductive pattern 54a and a hard mask pattern 56a, which are sequentially stacked on the substrate 50. Using the hard mask pattern 56a as an etch mask, the substrate 50 is etched to form a trench so as to define a plurality of parallel first active regions 60a. An insulation layer is filled within regions between

the stacked patterns and the trench, thereby forming a trench isolation layer 58. The patterns comprising the gate insulation pattern 52a, the conductive pattern 54a and the hard mask pattern 56a, which are sequentially stacked, are arranged on the first active regions 60a. The conductive pattern 54a includes 5 sidewalls 55 aligned to the sidewalls of the trench isolation layer 58. A portion of top of the trench device isolation layer 58 is recessed to reduce step differences between a substrate where a peripheral circuit and a logic circuit will be formed and device isolation layers. However, the recess needs to be controlled with respect to depth so that a top of the trench isolation layer 58 is 10 higher than a top of the conductive pattern 54a. If the top of the trench isolation layer 58 is lower than that of the conductive pattern 54a, sidewalls of conductive pattern 54a are oxidized by a thermal oxidation process for forming an oxide pattern on a floating gate pattern. If the sidewalls of conductive pattern 54a are oxidized, it is difficult to form a tip of the floating gate pattern 15 for Fowler-Nordheim tunneling.

As illustrated above, the gate insulation pattern 52a, the conductive pattern 54a and the hard mask pattern 56a, which are stacked on the substrate, may be formed with a mesh. Using the hard mask pattern 56a as an etch mask, the substrate 50 may be etched to form an active region with a mesh. The mesh shaped active region comprises a plurality of parallel first active regions 60a 20 and a plurality of second active regions 60b, which cross the first active regions 60a. Shared source regions of the NOR type FLASH memory device are formed in the second active regions 60b.

Referring to Figs. 5A, 5B and 5C, a photoresist pattern 61 is formed over the substrate 50. The photoresist pattern 61 includes a plurality of openings 62 parallel to the second active regions 60b. The hard mask pattern 56a and the device isolation pattern 58 are alternately exposed in the openings 62. A pair of openings 62 are disposed between the second active regions 60b. Using the photoresist pattern 61 as an etch mask, the hard mask pattern 56a is etched. Therefore, a top of the conductive pattern 54a is exposed in each of the openings 62 at regular intervals. Two parts of the top of the conductive pattern 54a are exposed on each of the first active region 60a between the second active regions 60b.

Referring to Figs. 6A, 6B and 6C, the photoresist pattern 61 is removed. As a result, the top of the conductive pattern 54a, which is defined by the device isolation layers 58 and the hard mask patterns 56a, is exposed over the substrate 50 like islands arranged along rows and columns. An oxide pattern 64 is formed on the exposed conductive pattern 54a. The oxide pattern 64 may be formed by performing an oxidation, oxidizing the exposed conductive pattern 54a. The oxide pattern 64 is formed having an elliptical cross-section due to a three dimensional-effect.

Referring to Figs. 7A, 7B and 7C, the hard mask pattern 56a is removed. As a result, the conductive pattern 54a is exposed over the first active region 60a and the second active region 60b. The oxide patterns 64 are disposed on the conductive patterns 54a at regular intervals.

Referring to Figs. 8A, 8B and 8C, using the oxide patterns 64 as an

etch mask, the conductive pattern 54a is etched. Thus, floating gate patterns 54b are formed on the first active region 60a at regular intervals. The floating gate pattern 54b includes sidewalls 55a aligned to sidewalls of the trench device isolation layer 58. The oxide pattern 64 is disposed on the top of the 5 floating gate pattern 54b. The oxide pattern 64 has an elliptical cross-section, so that tips may be formed at top edges of the floating gate pattern 54b. In the mesh shaped active region comprising the first and second active regions 60a and 60b, intersections of the first and second active regions 60a and 60b are disposed on a substrate and a pair of floating gate pattern 54b may be disposed 10 on the first active region 60a between the intersections.

Referring to Figs. 9A, 9B and 9C, a conductive layer is formed on an entire surface of a substrate with the floating gate patterns 54b and patterned to form a plurality of parallel word lines 68 crossing over the first active regions 60a. The word lines 68 lie on a portion of a top of the floating gate pattern 54b and on the first active region 60a adjacent to the floating gate pattern 54b. In addition, adjacent word lines 68 are disposed symmetrically. A pair of word lines 68 are disposed between the second active regions 60b forming a mesh shaped active region. A drain region is formed in the first active region 60a between the word lines 68 and a source region is formed in 15 the second active region 60b between the word lines 68.

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As a result, a split gate type FLASH memory device of the Fig. 2 can be formed.

According to an embodiment of the present invention, a floating gate

pattern may not be influenced by a proximity effect or a misalignment occurring during a photolithographic process because a trench device isolation layer is formed first. Further, the floating gate pattern is formed to have sidewalls aligned to sidewalls of the trench device isolation layer. Therefore, a 5 split gate type FLASH memory device can be formed to have substantially uniform cell characteristics in a cell array. In addition, floating gates of the memory cells connected to adjoining bit lines are isolated by the device isolation layer, so that a width of the device isolation layer can be reduced to improve integration of circuits.

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